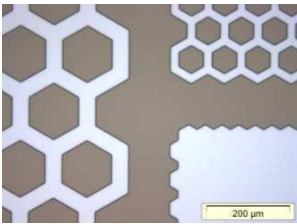


DisChem
CHEMISTRY FOR
ADVANCED LITHOGRAPHY

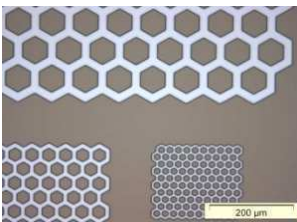
SURPASS

MICROLITHOGRAPHY RESIST ADHESION PROMOTERS

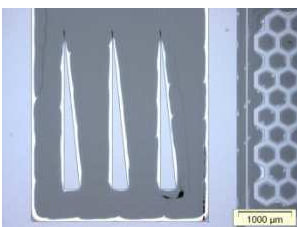
SurPass Advantage in Microlithography



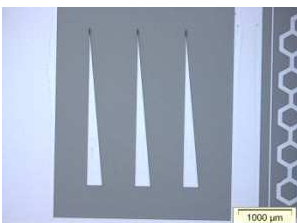
No Adhesion Promoter
Some Patterns Removed
During Resist Development



*Substrate Treated with
SurPass Adhesion Promoter*
Complete Precision Mask



No Adhesion Promoter
Resist Mask Undercut During
Etching



*Substrate Treated with
SurPass Adhesion Promoter*
Complete Precision Mask

- SurPass™ microlithography adhesion promoters provide maximum resist adhesion for advanced lithographic processes. Superior performance in optical and electron beam lithography applications.
- SurPass improves optical and e-beam resist adhesion on a broad range of substrate materials, including III-V materials, metals, and plastics.
- SurPass is a waterborne surface active agent that optimizes substrate surface energy for maximum resist adhesion, eliminating resist uplifting and undercutting during chemical processing.
- SurPass reduces the substrate zeta potential for improved resist process performance. Eliminates the pretreatment using organic solvents and wetting chemicals for increased throughput.
- Simple application via spray coating, spin coating or bath immersion makes SurPass ideal for application in new and existing manufacturing processes. Improved resist coating and process performance.
- SurPass is aqueous based and non-hazardous



*Please contact us to receive
additional product information and
no-charge product samples for
evaluation.*

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